

Notice of References Cited	Applicati n No. 09/330,418	Applicant(s) Taylor et al.	
	Examin r Sm J. Lee	Group Art Unit 1752	Pag 1 of 1

U.S. PATENT DOCUMENTS

☆		DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A		6,060,207	05-09-00	Shida et al.	430	176
B		5,786,131	07-28-98	Allen et al.	430	325
C		6,054,254	04-25-00	Sato et al.	430	322
D						
E						
F						
G						
H						
I						
J						
K						
L						
M						

FOREIGN PATENT DOCUMENTS

☆		DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
N		WO 97/33198	09-12-97	International (PCT)	Goodall et al.		
O		EP 0877 293 A2	11-11-98	European	Aoi et al.		
P							
Q							
R							
S							
T							

NON-PATENT DOCUMENTS

☆		DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
U		Johnson et al <u>Evaluation of TER-SYSTEM resist for 193 nm Imaging</u> Proceedings of SPIE-Int'l Society for Optical Engineering, Vol. 3049, Pg. 997-1009	March 1997
V			
W			
X			

\* A copy of this reference is not being furnished with this Office action.  
(See Manual of Patent Examining Procedure, Section 707.05(a).)